### Measurement of CO<sub>2</sub> laser absorption by thin plasma as a 13.5 nm EUV light source

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### Extensive studies have been made aiming at the the theoretical goal of EUV conversion efficiency (CE)



Y. Shimda, et al., APL 86, 051501 (2005)

S. Fujioka, et al., APL 92, 241502 (2008)

H. Mizoguchi et al., Proc. SPIE 8679, 86790A (2013)



Background

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# Two-color, double pulse scheme is widely adopted in EUV source for lithography



It is not clarified yet why CE is substantially increased, optimization plasma parameters or increase in laser absorption?



\*S.Fujioka *et al.*, APL 92, 241502 (2008).

# PredictionsDouble pulse scheme affords 6-8% EUV CEs, twicelarger than those given with a single pulse





A. Sunahara, OYO BUTSURI 83, 741 (2014)

### Predictions Theoretical predictions infer that increase in EUV CE is resulted from increase in laser absorption





### $\begin{array}{c|c} \mbox{Predictions} & \mbox{With increase in laser intensity, two distinct regions} \\ \mbox{appear for CE, dependent either on $T_e$ or $\eta_{labs}$} \end{array}$

$$\eta_{laser abs.} = 1 - \exp(-\tau L)$$
, where  $\tau \propto n_i n_e T_e^{-7/2} Z^2$ 





Sn droplet, L=150 $\mu$ m pre-plasma, CO<sub>2</sub> laser beam conversing at the center

#### Objectives

### 1. Experimental verification of CE vs. $\eta_{\text{labs}}$ 2. Optimization for higher $\eta_{\text{labs}}$ hence better CE

$$\eta_{laser abs.} = 1 - \exp(-\tau L)$$
, where  $\tau \propto n_i n_e T_e^{-7/2} Z^2$ 

Note: excessively long-scale plasma may result in reduction in CE due to "EUV self-absorption"





### We developed an integrating sphere for $\eta_{\rm labs}$ measurement of CO\_2 laser by plasma







### **Experiment** Multi-reflection of scattered light homogenizes its distribution on the inner surface



# Light intensity @detector $= \frac{\rho \Phi}{S} (1 + \rho + \rho^{2} + \rho^{3} + \rho^{4} + ... + \rho^{n-1})$ $= \frac{\Phi}{S} \frac{\rho}{1 - \rho}$

 $\Phi$ : light source power  $\rho$ : diffuse reflection factor S: surface area of integrating sphere



#### **EUV CEs and corresponding EUV spectra are** Experiment measured simultaneously with $\eta_{\text{labs}}$



### Plasma Shutter shortens pulse width of CO<sub>2</sub> laser used in the experiment





Experiment



### **Reduced signal from the detector indicates** absorption of CO<sub>2</sub> laser by plasma



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# **Experiment** Increase in CE and $\eta_{\text{labs}}$ show clear correlation between them, validating theoretical predictions



Delay time (ns)





- To improve EUV CE, increase of laser absorption rate is effective.
- $\square$  For validation, we have developed an integrating photosphere dedicated for CO<sub>2</sub> laser absorption measurement.
- We measured EUV CE at 13.5 nm and the drive laser absorption rate for single- and double-pulse cases, and found tight correlation between them.



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